



Applicant:

Sreenivasan, Sidlgata V.

App. No.:

10/614,716

GPAU:

1722

Filing Date:

July 7, 2003

Examiner:

Thukhanh T. Nguyen

Dkt. No.:

P90-32V30

Conf. No.:

7603

Conforming Template for Patterning Liquids Disposed on Substrates

INFORMATION DISCLOSURE STATEMENT

Mail Stop AMENDMENT **Commissioner for Patents** P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

The following information is submitted in compliance with Applicants' duty of disclosure and pursuant to 37 C.F.R. § 1.56, § 1.97 and § 1.98. The undersigned brings the patents, publications, applications or other information identified in the attached Form(s) PTO/SB/08A to the Examiner's attention in the above-identified application. It is respectfully requested that the cited information be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed during the period specified in § 1.97(c). Accordingly, the fee set forth in §1.17(p) is required and provided as shown below.

The Commissioner is hereby authorized to charge \$180.00 to Deposit Account Number 502650. Applicants do not believe that any additional fees are due, but if the Commissioner believes additional fees are due, the Commissioner is hereby authorized to charge any fees which may be required, or credit any overpayment, to Deposit Account Number 502650.

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Signed:____

Typed Name: Jennifer L. Cowlishaw

Date: 6 (6)

Respectfully Submitted,

Michael D. Carter Reg. No. 56,661

Registered Patent Agent

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/2	Substitute	for form 1449A	/PTO		Complete i	f Known
10	· \	NFORMATIO	N DISCLOS	URE	APPLICATION NUMBER	10/614,716
,	44 I/A. 494	TATEMENT			FILING DATE	07 July 2003
\ 1	/چ				FIRST NAMED INVENTOR	Sreenivasan et al
130	AT & TRADERIAS	ıse as many shee	ts as necessar	v)	GROUP ART UNIT	1722
		,			EXAMINER NAME	Emmanuel S. Luk
	Sheet	1	of	4	ATTORNEY DOCKET NUMBER	P90-32V30

	_			U.S. PATENT DOCUMEN	TS	
Examiner Initials*	Cite No.1	U.S. Patent Do	Kind Code ² (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
	G1	2005/0236360	A1	Watts et al.	10/27/2005	
	G2	6,399,406	B2	Chan et al.	6/4/2002	
	G3	6,605,849	B1	Lutwak et al.	8/12/2003	
	G4	6,607,173	B2	Westmoreland	8/19/2003	
	G5	7,037,639	B2	Voisin	5/2/2006	***
	G6	2006/0096949	A1	Watts et al.	5/11/2006	
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Substitute for form 1449A/PTO				Complete	Complete if Known		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				APPLICATION NUMBER	10/614,716		
				FILING DATE	07 July 2003		
				FIRST NAMED INVENTOR	Sreenivasan et al		
(use as many sheets as necessary)				GROUP ART UNIT	1722		
				EXAMINER NAME	Emmanuel S. Luk		
Sheet	2	of	4	ATTORNEY DOCKET NUMBER	P90-32V30		

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	G7	Translation of Japanese Patent 61-40845, 2/1/1986	Τ
		Translation of Japanese Patent 02-248480, 10/1/1990	\perp

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G8	Translation of Japanese Patent 02-248480, 10/1/1990	
G9	Translation of Japanese Patent 03-090345, 4/1/1991	
G10	Translation of Japanese Patent 09-278490, 10/1/1997	
G11	Abstract of Japanese Patent 03-090345, 4/1/1991	
G12	Abstract of Japanese Patent 09-278490, 10/1/1997	
G13	BIEN ET AL., Characterization of Masking Materials for Deep Glass Micromachining, J. Micromech. Microeng. 13 pp. S34-S40 1/1/2003	
G14	BRITTEN ET AL., Multiscale, Multifuncation Diffractive Structures We Etched into Fused Silica for High-Laser Damage Threshold Applications, Applied Optics, Vol. 37, No. 30 10/20/1998	
G15	FLETCHER ET AL., Microfabricated Silicon Solid Immersion Lens, Jounral of Microelectromechanical Systems, Vol. 10, No. 3 9/1/2001	
	G9 G10 G11 G12 G13 G14	Translation of Japanese Patent 03-090345, 4/1/1991 G10 Translation of Japanese Patent 09-278490, 10/1/1997 G10 Abstract of Japanese Patent 03-090345, 4/1/1991 G11 Abstract of Japanese Patent 09-278490, 10/1/1997 G12 BIEN ET AL., Characterization of Masking Materials for Deep Glass Micromachining, J. Micromech. Microeng. 13 pp. S34-S40 1/1/2003 BRITTEN ET AL., Multiscale, Multifuncation Diffractive Structures We Etched into Fused Silica for High-Laser Damage Threshold Applications, Applied Optics, Vol. 37, No. 30 10/20/1998 FLETCHER ET AL., Microfabricated Silicon Solid Immersion Lens, Journal of

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Sheet	3	of	4	ATTORNEY DOCKET NUMBER	P90-32V30

OTHER PRIO	R ART -	NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²

G16	KHANDAKER ET AL., Fabrication of Microlens Arrays by Direct Electron Beam Exposure of Photoresist, Pure Appl. Opt. 6, pp. 637-641 1/1/1997
G17	KIM ET AL., Replication Qualities and Optical Properties of UV-moulded Microlens Arrays, J. Phys. D: Appl. Phys. 36; pp. 2451-2456 1/1/2003
G18	KOBAYASHI ET AL., Batch Bulk-Mircomachined High-Precision Metal-On-Insulator Microspires and Their Application to Scanning Tunneling Microscopy, J. Micromech. Microeng. 14; pp. S76-S81 1/1/2004
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G20	KUNNAVAKKAM ET AL., Low-cost, Low-loss Microlens Arrays Fabricated by Soft-Lithography Replication Process, Applied Physics Letters, Volume 82, Number 8 2/24/2003
G2 ⁻	MANSELL ET AL., Binary-Optic Smoothing with Isotropic Etching, Applied Optics; Vol. 36, No. 20 7/10/1997
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G23	SANO ET AL., Submicron Spaced Lens Array Process Technology for a High Photosensitivity CCD Image Sensor, IEEE IEDM Dig.; pp. 283-286 1/1/1990
G24	TSUKAMOTO ET AL., High Sensitivity Pixel Technology for a 1/4 inch PAL 430k pixel IT-CCD, IEE Custom Integrated Circuits Conference 1/1/1996

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	G25	YONEDA ET AL., Translation of Japanese Patent 02-248480, Transparent Substrate with Water-Repellent and Antistaining Properties, and Structure Equipped Therewith 10/4/1990	
	G26	YONEDA ET AL., Translation of Japanese Patent 02-248480, Transparent Substrate Material with Water-Repllent and Anti-Staining Properties and Structure Equipped with Same 10/4/1990	
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